

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

PRO
JC979 U.S.
10/041026
12/28/01

APPL NUM 10041026	FILING DATE 12/28/2001	CLASS 118	SUBCLASS 1734	GAU	EXAMINER <i>Meek</i>
----------------------	---------------------------	--------------	------------------	-----	-------------------------

**APPLICANTS: Subramony Janardhanan; Yokota Yoshitaka; Iyer Ramaseshan; Luo
Lee; Chen Aihua;

1762

**CONTINUING DATA-VERIFIED:

** FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiners's initials			ATTORNEY DOCKET NO 006333
TITLE : Methods for silicon oxide and oxynitride deposition using single wafer low pressure CVD U.S.DEP.T.OF COMM/PAT.& TM-PTO-436L(Rev. 12-94)			

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G
ISSUE FEE		DRAWING		
Amount Due	Date Paid			
TERMINAL DISCLAIMER		Primary Examiner		
		Application Examiner		
PREPARED FOR ISSUE				
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.				

FILED WITH: DISK (CRF) CD-ROM
(Attached in pocket on right inside flap)